

Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No.	NOVLP094/NVLS-2919
	Application No.:	10/789,103
	Applicant	Wu et al.
	Filing Date	February 27, 2004
	Group	1762
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U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	1.	2003/0224156	12.2003	Kirner et al.			
	2.	2003/0111263	06.2003	Fornof et al.			
	3.	2002/0132496	09.2002	Ball et al.			
	4.	6,662,631	12.2003	Baklanov et al.			
	5.	2006/0145305	07.2006	Boyanov et al.			
	6.	7,098,149	08.2006	Lukas et al.			
	7.	2006/0040507	02.2006	Mak et al.			
	8.	2005/0230834	10.2005	Schmitt et al.			
	9.	2006/0105566	05.2006	Waldfried et al.			
	10.	2004/0018717	01.2004	Fornof et al.			
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	12.	2004/0249006	12.2004	Gleason et al.			
	13.	2005/0095840	05.2005	Bhanap et al.			
	14.	2006/0178006	08.2006	Xu et al.			
	15.	6,572,925 B2	06.2003	Zubkov et al.			
	16.	6,566,278 B1	05.2003	Harvey et al.			
	17.	6,413,583 B1	07.2002	Moghadam et al.			
	18.	6,407,013 B1	06.2002	Li et al.			
	19.	6,365,528 B1	04.2002	Sukharev et al.			

Foreign Patent or Published Foreign Patent Application

Examiner Initial		Document No.	Publication Date	Country or Patent Office	Class	Sub-Class	Translation	
							Yes	No
	20.	WO 03/052794 A2	26.06.2003	PCT				
	21.	WO 03/005429 A1	16.01.2003	PCT				

Other Documents

Examiner Initial	No.	Author, Title, Place (e.g. Journal) of Publication, Date
	22.	U.S. Office Action mailed November 30, 2006, from U.S Application No. 10/927,777 [Atty Dkt No. NOVLP106/NVLS-2930].

Examiner	Date Considered
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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	23.	U.S. Office Action mailed March 28, 2007, from U.S Application No. 10/820,525 [Atty Dkt No. NOVLP091/NVLS-2889].
	24.	U.S. Notice of Allowance and Fee Due mailed December 19, 2006, from U.S. Application No. 10/800,409. [NOVLP098/NVLS-2907]
	25.	U.S. Office Action mailed April 9, 2007, from U.S Application No. 10/800,409 [Atty Dkt No. NOVLP098/NVLS-2907].
	26.	Niu et al., "Methods for Improving the Cracking Resistance of Low-K Dielectric Materials," Novellus Systems, Inc., Appl. No. 11/376,510, filed March 14,2006, pages 1-28. [NOVLP099D1/NVLS-2896D1]
	27.	U.S. Office Action dated May 22, 2007, from U.S. Application No. 11/376,510 [Atty Dkt: NOVLP099D1/NVLS-2896D1]
	28.	U.S. Notice of Allowance and Fee Due mailed April 9, 2007, from U.S. Application No. 10/927,777. [NOVLP106/NVLS-2930]
	29.	Allowed Claims from U.S. Application No. 10/927,777. [NOVLP106/NVLS-2930]
	30.	U.S. Final Office Action mailed April 3, 2007, from U.S Application No. 10/941,502 [Atty Dkt No. NOVLP107/NVLS-2932].
	31.	U.S. Notice of Allowance and Fee Due mailed December 20, 2005, from U.S. Application No. 10/860,340. [NOVLP099/NVLS-2896]
	32.	Wu et al., "PECVD Methods for Producing Ultra Low-K Dielectric Films Using UV Treatment," Novellus Systems, Inc., Appl. No.11/608,056, filed December 7, 2006, pages 1-34. [NOVLP196/NVLS-3238]
	33.	Wu et al., "Methods for Improving Performance of ODC Films with Dielectric Constant < 4.0," Novellus Systems, Inc., Appl. No. 11/693,661, filed March 29, 2007, pages 1-46. [NOVLP200/NVLS-3269]
	34.	Allowed Claims from U.S. Application No. 10/860,340. [NOVLP099/NVLS-2896]
	35.	U.S. Notice of Allowance and Fee Due mailed September 19, 2007, from U.S. Application No. 10/800,409. [NOVLP098/NVLS-2907]
	36.	Allowed Claims from U.S. Application No. 10/800,409. [NOVLP098/NVLS-2907]
	37.	U.S. Office Action mailed October 4, 2007, from U.S Application No. 10/820,525 [Atty Dkt No. NOVLP091/NVLS-2889].
	38.	U.S. Office Action mailed October 29, 2007, from U.S Application No. 11/764,750 [Atty Dkt No. NOVLP106D1].

Examiner	Date Considered
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